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(Received 16 February 2018; revised manuscript received 13 June 2018; published 2 July 2018)

Vanadium dioxide (VO₂), an archetypal correlated-electron material, undergoes an insulator-metal transition near room temperature that exhibits electron-correlation-driven and structurally driven physics. Using ultrafast temperature- and fluence-dependent optical spectroscopy and x-ray scattering, we show that multiple interrelated electronic and structural processes in the nonequilibrium dynamics in VO₂ can be disentangled in the time domain. Specifically, following intense subpicosecond terahertz (THz) electric-field excitation, a partial collapse of the insulating gap occurs within the first picosecond. At temperatures sufficiently close to the transition temperature and for THz peak fields above a threshold of approximately 1 MV/cm, this electronic reconfiguration initiates a change in lattice symmetry taking place on a slower timescale. We identify the kinetic energy increase of electrons tunneling in the strong electric field as the driving force, illustrating a promising method to control electronic and structural interactions in correlated materials on an ultrafast timescale.

DOI: 10.1103/PhysRevB.98.045104

I. INTRODUCTION

Ultrafast control of fundamental electronic and structural interactions in strongly correlated oxide materials is a promising avenue toward realizing the next generation of faster and more energy-efficient electronic devices [1–5]. VO₂ is viewed as a potential key building block for such devices due to its near-room-temperature insulator-metal transition (IMT), which can be triggered on a subpicosecond timescale [6–8]. Such rapid switching, along with dramatic changes in the electrical and optical properties [9–11], gives rise to a multitude of novel possibilities for logic and memory devices, some of which could potentially be transformative to modern technology and computing [2,12,13].

While a full understanding of the IMT in VO₂ remains a challenge, it is clear that both electron-electron correlations and electron-lattice interactions are relevant [14,15]. What is less clear is the extent to which correlation and structure can be disentangled, although evidence is mounting that a monoclinic metallic phase can be obtained under appropriate conditions [16–20]. As such, a concerted effort aimed at understanding and achieving decoupling of the electronic and structural transitions in VO₂ has gained significant momentum [17,18,21]. To further investigate these intriguing possibilities, it is crucial to interrogate the dynamics of the electronic and lattice structure under well-controlled excitation conditions and on the same samples.

Along these lines, recent developments in the field of ultrashort high-field terahertz (THz) pulse generation opened the door for triggering the IMT in VO₂ by nonresonant THz excitation of the electronic system at photon energies far...
FIG. 1. Static resistance and x-ray diffraction characterization of the 200-nm VO$_2$(001) film deposited on Al$_2$O$_3$(10Ì¬10) substrate. (a) Resistance versus temperature curves (blue) showing the insulator-metal transition during both heating and cooling cycles for the unpatterned film. Also shown is the intensity of the VO$_2$(002)$_R$ diffraction peak measured with synchrotron radiation and plotted as a function of temperature. (b) High-resolution Cu $K\alpha$ $\theta$-2$\theta$ x-ray diffraction pattern showing both the substrate and the film Bragg peaks. (c) Static near-IR (800-nm) transmission versus temperature measured on the unpatterned film during the heating cycle. Temperature scale was adjusted to account for the difference in the temperature calibration between the different sample holders. (d) Resistance versus temperature curves measured after patterning the VO$_2$ film with Au metamaterials. Starting (base) temperature for the pump-probe measurements (324 K) is marked with a yellow circle. (e) Temperature-dependent x-ray diffraction scans of the VO$_2$ film peak carried out at LCLS prior to time-resolved measurements.

below any of the relevant optical phonon modes or interband transitions [20]. A THz-pump THz-probe time-resolved study showed that the IMT in VO$_2$ can, in fact, be initiated with a THz electric field [22]. This experiment revealed that the transition is a multistep process. However, the subpicosecond electronic dynamics could not be temporally resolved nor were the structural dynamics measured.

We use THz excitation to initiate the IMT, which is probed using near-IR spectroscopy in combination with ultrafast hard x-ray scattering at the Linac Coherent Light Source (LCLS) [23,24]. We demonstrate that the various processes comprising the electric-field-induced electronic and structural phase transitions in VO$_2$ can occur on different timescales. Electronic structure switching in a VO$_2$(001) film is observed to be virtually simultaneous with the subpicosecond metamaterial-enhanced THz pulse and is induced by electric-field-assisted tunneling of valence electrons into the conduction band. For sufficiently high electric fields, $E \geq E_{\text{threshold}}$ (~1 MV/cm), this triggers the onset of the full transition to the rutile metallic state.

II. EXPERIMENT

A. Thin film and metamaterials synthesis

For our experiment, a high-quality crystalline 200-nm VO$_2$(001) thin film was grown epitaxially on an Al$_2$O$_3$(1010) substrate by pulsed laser deposition [25]. The temperature-dependent IMT was verified by electrical transport measurements in a Quantum Design DynaCool cryostat using a four-terminal sensing method with aluminum wire contacts that were ultrasonically bonded directly to the surface of the VO$_2$ films [see Fig. 1(a)]. Epitaxy and the monoclinic-rutile structural transition were verified with high-angular-resolution (<0.01°) x-ray diffraction (XRD) measurements using a Bruker D8 Discover system [see Fig.1(b)] and high-resolution temperature-dependent XRD measurements carried out at the 7ID-C beamline of the Advanced Photon Source [see Fig. 1(a)]. For the latter, the sample was mounted on a temperature-controlled stage with a control range from 250 to 450 K. The lattice Bragg peaks were characterized by $\theta$-2$\theta$ scans in a six-circle diffractometer with a monochromatic 6.5-keV x-ray beam and an area detector (PILATUS 100 K). Figures 1(a) and 1(b) show the results of these measurements confirming the bulklike nature of our VO$_2$ films with the expected IMT and monoclinic-rutile (M1-R) structural transformation at 337 K, as defined by the heating curve. Static temperature-dependent near-IR (800-nm) transmission measurements confirm the optical response of the film, characterized by the decrease in transmission intensity across the IMT [15] [see Fig. 1(c)]. Metamaterial antennae consisting of an array of 8.5-µm-wide Au lines [see Figs. 1(d) and 2(a)–2(c)] were deposited on the sample via optical lithography in order to enhance the THz $E$ field at the sample, as described below. Transport measurements after the deposition [see Fig. 1(d)] show more
FIG. 2. THz metamaterials simulations and characterization. (a) Schematic diagram depicting relative scales of the metamaterials grid pattern. THz beam footprint on the sample (1.6 mm × 1.0 mm) and the x-ray beam footprint on the sample (0.8 mm × 0.5 mm). (b) SEM image of the optimized periodic metamaterials pattern showing wider Au lines (8.5 µm) and narrower (1.5 µm) gaps exposing the VO₂ film (dark contrast). Cross-sectional profile of the structure is shown below. 2-nm-thick Cr layers are used to optimize the adhesion and lift-off steps during the lithography process. (c) High-resolution SEM image of the 1.5-µm-wide metamaterial gap exposing the VO₂ film. (d) Simulated time-dependent THz field (red) in the metamaterial gaps using experimental data (black) as the input. (e) THz field enhancement as a function of position within the 1.5-µm gap, showing an average field enhancement of ×4. The chosen geometry represents a compromise between substantial field enhancement for the THz pump and fill fraction of VO₂ for adequate sampling using the x-ray probe. The chosen design further minimizes nonuniformity of the electric field inside of the gap.

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than four orders of magnitude change in resistance across the IMT, thus indicating no degradation of film quality due to the fabrication process. Temperature-dependent XRD measurements carried out at LCLS prior to the time-resolved measurements confirm the structural transition of the patterned film [see Fig. 1(e)].

The optimal metamaterial geometry and dimensions were designed using the CST MICROWAVE STUDIO full-wave electromagnetic solver (see Fig. 2). The simulations used the time-domain solver, performing a geometric parameter sweep to achieve the maximum terahertz field enhancement [see Fig. 2(d)] while maintaining compatibility with the experimental constraints. The antenna geometry was specifically optimized for the LCLS experiment, in order to provide a 4× enhancement across the spectrum of the incident THz pulse E field (nominally up to 0.4 MV/cm) inside the 1.5-µm antenna gap [see Fig. 2(e)]. Thus, maximum E-field peak strengths of up to 1.6 MV/cm (sufficient to initiate the IMT [22]) were achieved inside the gap at normal incidence. It is important to note that this maximum value is approximately 2.2× lower than the damage threshold field (~3.5 MV/cm) reported in the prior study conducted for a similar film thickness, substrate material, and the THz generation scheme [22]. Thus, no permanent damage to the film was expected to occur during the THz excitation.

Standard optical lithography techniques were used to fabricate the abovementioned metamaterials on a VO₂ film. Spin coating of 1.33-µm-thick photoresist (SPR670) and subsequent UV exposure and development was used to define the metamaterials. The part of the VO₂ film which was not covered by photoresist was milled away using an Ar ion beam with 100-eV energy. Metamaterial antenna electrodes composed of 2-nm Cr/200-nm Au/2-nm Cr were deposited on the etched area by ion-beam deposition. After lift-off, the patterned sample was rinsed using isopropyl alcohol. Scanning electron microscopy (SEM) images of the resultant optimized periodic
metamaterial pattern and its cross-sectional schematics are shown in Figs. 2(a)–2(c).

### B. Time-resolved measurements

Ultrafast THz-pump–near-IR and hard x-ray probe measurements were carried out nonconcomitantly in the experimental geometries shown in Fig. 3(a). Both experiments used single-cycle THz-pump pulses with peak $E$ field up to 0.4 MV/cm and central frequency of 0.6 THz, generated by the 20-mJ output of a 1-kHz, 100-fs Ti:sapphire amplifier via optical rectification in a LiNbO$_3$ crystal using the tilted pulse-front technique [26–28].

THz-pump–near-IR-probe measurements of the electronic structure evolution were carried out in the collinear normal-incidence geometry as shown in Fig. 3(a). Part of the 800-nm beam generated by the Ti:sapphire amplifier was utilized as a probe of the sample transmission with a standard ultrafast InGaAs diode used as a detector. The wavelength of 800 nm is sensitive to the interband transitions from the occupied $d_{\parallel}(a_{1g})$ orbitals across the insulating gap and into the unoccupied $\pi^*$ ($e_{\pi}^\ast$) states [see Fig. 3(b)]. During the IMT, bonding and antibonding $d_{\parallel}$ states merge into a single band, while the $\pi^*$ band shifts to lower energies. The two bands overlap in energy, and the resulting nonzero density of states at the Fermi level accounts for the metallic behavior and change in the transmission signal at 800 nm [15]. The THz-pump–near-IR-probe response of the substrate is negligible compared to that of the VO$_2$ film, as demonstrated by measurements on a bare Al$_2$O$_3$(10$\bar{1}$0) sample within the same experimental setup (see Fig. 4).

THz-pump–x-ray probe structural dynamics experiments were carried out at the x-ray pump-probe instrument of the LCLS. In order to measure the time-resolved lattice response of VO$_2$, the THz pump was incident on the sample collinearly with the 7-keV free-electron laser x-ray beam at an incidence angle of $\sim$38°, which is the Bragg angle for the rutile (002) diffraction peak, sensitive to the changes in atomic-layer spacing along the $c_R$ axis [see Fig. 3(a)]. In the static case, a temperature-induced transition results in a decay of the monoclinic (40$\bar{2}$) peak (M1) and growth of the rutile (002) peak (R), which is offset in $q$ space by $\sim$0.02 Å$^{-1}$ due to the change in the average lattice spacing [see Fig. 3(c), as well as Fig. 1(e)]. A large two-dimensional position-sensitive detector [29] enables $\theta$-$2\theta$ spectroscopic measurements of the rutile and monoclinic diffraction peaks by rotating the sample ($\theta$) and measuring the intensities of the specular Bragg reflection spots (R and M1) while tracking their movement across the detector ($2\theta$). The structural transition accompanied by dimerization of the neighboring V atoms along the out-of-plane $c_R$ direction and tilting of the resultant V-V dimers along the rutile [110] and [110] directions is depicted schematically in Fig. 3(d).
FIG. 4. Substrate response to the THz $E$-field pump. THz-pump–near-IR-probe change in transmission response for the bare Al$_2$O$_3$ substrate (blue) compared to that of a 200-nm VO$_2$ film on the same Al$_2$O$_3$ substrate (magenta). The Al$_2$O$_3$ substrate shows almost no measurable response to the THz pulse, except for small-amplitude ps-scale modulations between 2 and 6 ps (outset) which are orders of magnitude weaker than the VO$_2$ response.

### III. RESULTS

#### A. Electronic structure evolution

Figure 5 shows the electronic response to THz excitation as measured by optical transmission. The onset of the electronic response is observed simultaneously with the THz excitation pulse shown in Fig. 5(a) exhibiting a rich multistep evolution. In order to decouple the distinct electronic processes taking place within the first several picoseconds following THz excitation, we carried out a series of temperature- and fluence-dependent THz-pump–near-IR-probe measurements. Figures 5(a) and 5(b) depict time-delay traces of normalized near-IR transmission (at $\lambda = 800$ nm) recorded for two different temperatures and for several THz-pump excitation strengths expressed in terms of the peak $E$ field. The THz pulse waveform (not enhanced by metamaterials) was measured and calibrated via standard electro-optic sampling [30], as shown in the outset plot above Fig. 5(a) displaying the profile observed in prior studies [22,31,32]. The maximum achieved enhanced peak $E$ field of 1.6 MV/cm was normalized to 100%, and the attenuated peak $E$ fields of 80% (1.28 MV/cm), 60% (0.96 MV/cm), etc. with respect to this nominal value were obtained using a pair of rotatable THz wire-grid polarizers.

Figure 5(a) shows $E$-field-dependent pump-probe time-delay traces recorded at room temperature ($T_1 = 300$ K), which is 37 K below the measured $T_{\text{IMT}}$ of 337 K. As the data show, at temperatures far below the onset of the IMT, the dynamics is dominated by processes confined to the temporal window when the THz pulse is present in the sample ($\sim 1$ ps). There is a substantial increase in the optical transmission of the film that follows in shape the square of the THz pulse waveform. This suggests an $E$-field-driven modification of the electronic structure leading to a transient decrease of the near-IR absorption, analogous to what has been observed in dielectrics by Schultz et al. [3]. Essentially, a Wannier-Stark-like renormalization of the band structure results in a decrease in the joint density of states between occupied and unoccupied levels, leading to the observed transmission increase [33–38].

The Wannier-Stark-like renormalization is independent of sample temperature and displays a nonlinear dependence on the strength of the $E$ field [Fig. 5(c)], consistent with prior experimental observations as well as with the theoretical picture [3,38]. It is important to note that additional time-resolved experiments utilizing direct probes of the valence and conduction bands with sub-THz-pulse-length resolution are required to unambiguously confirm the proposed picture of the Wannier-Stark effect assisting the IMT.

At strong enough fields, Wannier-Stark-like renormalization results in the mixing of the valence- and conduction-band electronic states leading to Zener-Keldysh-like interband tunneling of valence electrons at the valence-conduction-band anticrossings [38–42]. We observe the experimental fingerprint of such a nonthermal electronic tunneling process, characterized by an abrupt decrease in transmission due to prompt metalization coinciding with the transient peak attributed to the band renormalization. We emphasize that this effect is simultaneous with the exciting THz pulse and ceases once the THz pulse is no longer present in the sample (past $t = 1$ ps). Importantly, this steplike tunneling feature is (unlike the $E$-field-dependent band renormalization) highly temperature dependent as evidenced by the differences between the data at $T_1 = 300$ K [Fig. 5(a)] and $T_2 = 324$ K [Fig. 5(b)]. We speculate that the apparent increase in the efficiency of the interband tunneling processes near the $T_{\text{IMT}}$ [Fig. 5(b)] could be attributed to changes in the electronic structure and, in particular, to the softening of strong electronic correlations at the onset of the IMT observed recently via temperature-dependent polarized x-ray absorption spectroscopy [43,44]. An unambiguous determination of the origin of this phenomenon requires an in-depth time-resolved temperature-dependent study.

At room temperature ($T_1 = 300$ K), the interband tunneling at high THz peak fields induces a stable long-lived state with partially collapsed band gap that persists for picoseconds after the THz pulse [Fig. 5(a)]. This observation is consistent with the recent work by Mayer et al. [45], wherein the IMT in VO$_2$ was induced by multi-THz transients. As we tune the temperature closer to $T_{\text{IMT}}$ (up to $T_2 = 324$ K), tunneling becomes more efficient [see respective delay traces in Fig. 5(b)] without, however, altering the temporal behavior. Finally, above a peak THz field of 1.0 MV/cm ($\pm 0.1$ MV/cm), a third process
FIG. 5. Electronic dynamics in a VO$_2$ thin film undergoing an IMT induced by an ultrafast THz electric-field pulse [shown in the outset above panel (a)]. (a) The $E$-field-dependent electronic response measured via near-IR transmission at room temperature ($T_1 = 300$ K) is dominated by a sharp transient increase in transmission consistent with Wannier-Stark-like band renormalization [3,33–38]. For high fluences (e.g., purple delay trace) this process is accompanied by a weak concomitant drop in transmission, characteristic of sudden metallization of VO$_2$ via direct Zener-Keldysh-like interband tunneling [38–42]. (b) At the onset of the IMT ($T_2 = T_{IMT} - 13$ K) tunneling processes become more efficient, and above a threshold peak field of approximately 1 MV/cm the absorbed energy density is sufficient to initiate lattice dynamics (see Fig. 7). (c) Wannier-Stark peak amplitude exhibits a nonlinear dependence on the peak $E$ field with minimal temperature dependence between 300 and 324 K. (d) The subsequent dynamics can be pictured more clearly by subtracting off the temperature-independent dynamics. In this plot, data shown in panel (a) are subtracted from the corresponding data from panel (b). (e) $E$-field dependence of the amplitudes characterizing the pulse-width-broadened step and exponential functions suggests different electronic origins of the two processes and reveals the threshold onset of the exponential feature. (f) Schematic representation of the early-time electronic dynamics. The scenarios discussed in the text are visualized by depicting schematic energy levels (metallic vs insulating) for an atomic chain.

sets in, characterized by an exponential decrease with time in near-IR transmission after $t = 1$ ps. Above this threshold field value, this exponential process begins to dominate the IMT dynamics, driving the film toward the metallic phase over a multipicosecond timescale. Observation of this slower dynamics is consistent with the measurements by Liu et al. [22] (also obtained at the temperature of 324 K), where the energy density deposited by a THz pulse was sufficient to drive electron-phonon thermalization and heating toward (and above) $T_{IMT}$. We consider this picture in more detail in the following paragraphs.

Since the Wannier-Stark-like renormalization does not show a significant temperature dependence, as evidenced by the overlaid plots of the $E$-field-dependent peak intensities for 300 and 324 K in Fig. 5(c), we can subtract this contribution from the higher-temperature data using corresponding room-temperature spectra. This data analysis enables the extraction of the temporal shape and amplitude of the tunneling breakdown dynamics in VO$_2$ during the first picosecond of the IMT. As shown in Fig. 5(d), the abrupt decrease in transmission follows a simple step function broadened by the THz pulse duration, consistent with ultrafast nonthermal field-induced tunneling as described above [45]. For high THz fluences this process is followed by slower metallization dynamics characterized by an exponential decay where the band gap collapses with a time constant of approximately 6 ps [Fig. 5(d)].

Figure 5(e) shows the amplitude versus field strength of the steplike and exponential features from Fig. 5(d). The points were obtained by simultaneous fitting of the delay traces with the combination of a simple step function broadened by the THz pulse duration (fixed value of 1 ps) and an exponential decay function. Best-fit values of the step and exponent amplitudes, as well as the corresponding error bars, are shown in Fig. 5(e) for all measured delay traces. Typical example of the fit (for $E = 1.6$ MV/cm) is shown as the dashed curves overlaying the experimental data (purple symbols) in Fig. 5(d).
FIG. 6. THz-pump–near-IR-probe change in transmission for VO$_2$/Al$_2$O$_3$ for longer time delays. Transmission at 800 nm decays monotonically, with the exception of a sharp feature observed at ca. +9.5 ps time delay, which is an echo artifact, arising due to the reflection of the THz pulse from the backside of the substrate in the normal-incidence geometry.

A clear difference in the functional dependence of these two features suggests different electronic origins. The step-function amplitude [red markers in Fig. 5(e)] exhibits exponential behavior (versus $E$ field) consistent with nonresonant Zener tunneling [39,41]. It is measurable even at moderate peak fields (0.32 MV/cm). Best fit to an exponential function is shown with a red solid line. In contrast, a clear threshold behavior is observed for the exponential amplitude (blue curve). The threshold field sufficient to drive the electronic system through the point of no return is estimated to be approximately 1 MV/cm (blue/purple marker). Above this critical field, the IMT progresses exponentially with a steep field dependence (purple markers) resulting in metallization of a significant fraction of the film.

While Fig. 5 focuses on the time delays relevant to the key processes involved in the initiation of the IMT in VO$_2$ (0–8 ps), in Fig. 6 we show a typical THz-pump–near-IR-probe trace collected for longer time delays (up to 500 ps), which include further growth and subsequent relaxation of the metallic phase. This delay trace, showing the long-term electronic response to THz excitation, can be directly compared to the structural dynamics evolution plots shown in the next section. We note that during the growth phase (1–175 ps) the 800-nm transmission decays monotonically, with the exception of a sharp feature observed at ca. +9.5 ps. This feature is an “echo” artifact, arising due to the reflection of the THz pulse from the backside of the substrate in the normal-incidence geometry.

B. Structural dynamics

Figure 7 shows the temporal evolution of the monoclinic–rutile structural transformation during the first 500 ps following THz-pump excitation for two sample base temperatures. Data points were obtained by measuring the intensities of the monoclinic (M1) and rutile (R) scattering peaks via $\theta$–$2\theta$ scans (shown in units of $q_\theta$ in the insets) at a given time delay. In order to account for any instrumental drift during the scan, every forty-first shot was recorded without the excitation laser pulse ($I_{OFF}$) and used as a continuous equilibrium “laser-off” reference. Detector data for each x-ray pulse were corrected (via simple subtraction) by the reference dark-current detector image and then normalized using the shot-to-shot x-ray pulse intensity monitor [46]. In order to account for any additional intensity fluctuations between individual pulses, a flat diffuse detector background sampled from a region on the image close to but separated from the M1 and R peaks was subtracted for each shot. A weighted average of all the shots for each value of $q_\theta$ was then calculated based on the x-ray pulse intensity monitor. The resultant experimental $\theta$–$2\theta$ spectra (circular markers in the insets) were then fitted using simple Gaussians (solid lines) to obtain peak intensities as functions of time delays. For the monoclinic peak, since the intensity changes are significantly smaller compared to the absolute intensities of the peak in the ground state (~73–97%), we show the angle-resolved intensity change spectra ($I_{ON}$–$I_{OFF}$). These were obtained by subtracting the reference $\theta$–$2\theta$ scans recorded without the excitation laser pulse ($I_{OFF}$) from the normal scans obtained with the laser pulse ($I_{ON}$). Upper inset in panel (d) shows the initial suppression of the rutile x-ray diffraction signal [absent in (b)] for the first 15 ps due to preferential heating of the lattice in those metallic regions.
rutile phase. The measurements shown in panels 7(c)–7(d) were carried out at a higher base temperature of 324 K \( (T_{\text{IMT}} - 5 \text{ K}) \), at which approximately 27% of the VO\(_2\) film is already transformed from the monoclinic to the rutile phase. While the overall shape of the monoclinic and rutile data is qualitatively similar for the two base temperatures [see Sec. IV for further discussion], there is a clear deviation for early times for the rutile data [see top inset of Fig. 7(d)]. The initial dip in the rutile diffraction intensity at 324 K demonstrates increased thermal lattice heating following the THz pump, likely due to THz-driven currents in the metallic regions (see discussion below).

**IV. DISCUSSION**

The results of our THz-pump–near-IR-probe experiments suggest the following scenario [Fig. 5(f)]. Below \( E_{\text{threshold}} \), the applied field induces Wannier-Stark band renormalization accompanied by Zener-Keldysh-like interband tunneling. At times longer than the pulse duration, the flat plateau that is observed in Fig. 5(a) arises from carriers that have tunneled into the conduction band and do not recombine for many picoseconds. In the language of correlated electron materials, the tunneling creates double-occupancy sites with a finite density of states at \( E_F \) —that is, there is a partial collapse of the Mott-Hubbard gap. In this \( E \)-field range below \( E_{\text{threshold}} \) and on the timescales accessed in Fig. 5 there is no observable increase or decrease in the signal beyond 1 ps. As we raise the sample temperature closer to the onset of the IMT (to \( T_2 = T_{\text{IMT}} - 13 \text{ K} \)) electronic correlations are softened [43]—a phenomenon which is unique to strongly correlated oxides, such as VO\(_2\), and not observed for a typical band insulator [3]. This leads to more efficient tunneling accompanied by a concurrent band-gap collapse when double occupancies are formed, and to a commensurate increase in the carrier density. Subsequently, the THz electric field accelerates these carriers, which then relax through electron-phonon collisions. For sufficiently high fields, above \( E_{\text{threshold}} \), this increases the lattice temperature initiating the IMT toward the rutile metallic phase. This corresponds to the exponentially decreasing term in Fig. 5(d) (magenta line).

In the grazing-incidence Bragg geometry necessary for the THz-pump–x-ray probe measurements [Fig. 3(a)], the enhanced \( E \)-field peak strength is determined to be 1.0 MV/cm \( \pm 0.1 \text{ MV/cm} \) using basic geometric considerations. At this field strength, the THz excitation drives VO\(_2\) toward the threshold above which electron-lattice interactions trigger the change in lattice symmetry [Figs. 5(d) and 5(e)]. Thus, the long-term (hundreds of picoseconds) structural dynamics shown in Figs. 7(a) and 7(b) is characterized, as expected, by the decay of the monoclinic phase (a) and a concomitant growth of the rutile phase (b). We note that during the first \( \sim 30 \text{ ps} \) of the THz-driven transition the change in lattice symmetry manifests, initially, as an increase of the monoclinic peak intensity. Specifically, the monoclinic peak intensity grows for \( \sim 30 \text{ ps} \) before eventually decreasing and, further, is not accompanied by a decrease in the intensity of the rutile peak. This suggests that a new monoclinic phase of VO\(_2\), characterized by a higher structure factor, may be forming at the onset of the structural transition. A possible two-step scenario, involving initial dilation of the V-V dimers at the onset of the transition, has been proposed in a prior ultrafast electron diffraction study of the optically induced IMT in VO\(_2\) [47]. However, the observed timescales for the optically induced dynamics in Ref. [47] differ significantly from ours (THz induced). Thus, further investigations involving concomitant measurements of additional diffraction peaks that are sensitive to the in-plane lattice constants of the film are required to unambiguously solve for the motion of the V-V dimers during the onset of the transition. Such measurements were not possible in the current experimental setup.

Finally, both electronic and structural phase-separation scenarios in VO\(_2\) have been previously observed both statically and dynamically during temperature-driven transition by scanning near-field optical and infrared microscopy [48–50] and scanning probe x-ray diffraction [51]. Thus, the presence of a small amount of rutile phase (approximately 2.7%) at 324 K \( (T_{\text{IMT}} - 5 \text{ K}) \) raises an important question as to whether selective heating due to THz-driven currents in the conducting regions and subsequent thermal diffusion could account for the observed slow (hundreds of picoseconds) structural dynamics. To address this question, we show in Figs. 7(c) and 7(d) time-resolved XRD data obtained at a higher base temperature of 324 K \( (T_{\text{IMT}} - 5 \text{ K}) \), at which approximately 27% of the VO\(_2\) film is already transformed from the monoclinic to the rutile phase, and thus a much higher metallic volume fraction can be affected by the THz pump. As can be unambiguously seen in Fig. 7(d) and its top inset, during the first 15 ps the rutile XRD signal is attenuated due to preferential heating of the lattice in these regions (Debye-Waller effect). In contrast, for the lower base temperature in Figs. 7(a) and 7(b) no such effect is observed within the uncertainty of the measurement. This suggests that preferential excitation of the already present metallic rutile puddles requires a certain size of such regions, as it is satisfied at 324 K. However, this mechanism can be ruled out to be the dominant process for the much smaller rutile patches present at 324 K. Finally, heating of the Au metamaterial stripes can be neglected since heat transport, with typical propagation speeds on the order of 1 nm/ps [52], takes hundreds of ps to cover the whole VO\(_2\) material in the 1.5-μm-wide metamaterial gap. We also would like to point out that the different amount of rutile VO\(_2\) generated by THz heating for the two base temperatures shown in Fig. 7 points to a more efficient absorption of THz energy into preexisting rutile compared to monoclinic VO\(_2\) areas. Overall, the THz energy absorbed in our experiment is smaller than that for typical optical excitation energies [22].

Further investigations of the subpicosecond lattice dynamics near time zero are required to determine the three-dimensional lattice response during the intense THz pulse, which reaches its peak value at \( t = +0.2 \text{ ps} \) (within a 2-ps-long window between the measured time delays of −1 and +1 ps). Additional high-resolution and high-statistics time-resolved x-ray diffraction measurements should be carried out to determine the lattice response during the initial stages of the IMT (1–8 ps). Furthermore, the possible existence of the intermediate M2 phase, shown to be present in strained films [10], must be considered in future studies of strained films. Finally, effects of the multiple THz reflections from the back surface of the substrate need to be considered at longer delay times.
V. SUMMARY AND CONCLUSIONS

In conclusion, our experiments show that various processes in the nonequilibrium electronic and structural dynamics in VO$_2$ can be disentangled in the time domain by inducing the IMT with an intense nonresonant THz pulse and probing with near-IR and hard x-ray pulses. The primary trigger for the electric-field-initiated transition is shown to be Zener-Keldysh-like tunneling assisted by Wannier-Stark-like band renormalization. At temperatures sufficiently close to $T_{\text{IMT}}$ and for THz peak fields above a threshold of approximately 1 MV/cm the THz electric field accelerates the carriers, which increases the lattice temperature initiating the transition toward the rutile metallic phase. This is a result of softening of electronic correlations and of efficient energy transfer to the lattice from carrier acceleration and electron-phonon collisions. The rich multidimensional landscape resulting from the interplay of the Mott and Peierls physics provides a pathway to achieving efficient THz switching in strongly correlated oxides via ultrafast electric-field excitation.

ACKNOWLEDGMENTS

Research at Stanford was supported through the Stanford Institute for Materials and Energy Sciences (SIMES) under Contract No. DE-AC02-76SF00515. Use of the LCLS, SLAC National Accelerator Laboratory, is supported by the U.S. Department of Energy, Office of Science, Office of Basic Energy Sciences under Contract No. DE-AC02-76SF00515. M.C.H. is supported by the U.S. Department of Energy, Office of Science, Office of Basic Energy Sciences, under Award No. 2015-SLAC-100238-Funding. Research by the Massachusetts Institute of Technology group was supported in part by Office of Naval Research Grant No. N00014-13-1-0509 and National Science Foundation Grant No. CHE-1111557. H.W. and Y.Z. acknowledge the support by U.S. Department of Energy, Office of Science, Office of Basic Energy Sciences (DOE-BES), Materials Sciences and Engineering Division. Use of Advanced Photon Source was supported by DOE-BES, under Contract No. DE-AC02-06CH11357. R.D.A. acknowledges support from the U.S. Department of Energy, Office of Science, Office of Basic Energy Sciences under Grant No. DE-FG02-09ER46643. E.A. acknowledges support from Fundação para a Ciência e a Tecnologia, Portugal, through Doctoral Degree Fellowship No. SFRH/ BD/ 47847/ 2008. J.B. is supported by the DFG under Grant No. SFB762. S.B. acknowledges support from the Knut and Alice Wallenberg Foundation.

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